

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	161	(lithography with tool) and (tool with correct\$3) and (select\$3 with position with field exposure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:46
L2	0	1 and (record\$3 with test with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:47
L3	2	1 and (monitor\$3 with test with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:47
L4	2	"6737207".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:52
S1	0	10/604051	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:15
S2	0	electron with beam with lithography with tool with test with pattern with cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:31
S3	284	electron with beam with lithography with tool	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 19:40
S4	0	(electron with beam with lithography with tool) and (three with elongat\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 17:22
S5	0	(electron with beam with lithography with tool) and (three with elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 19:48
S6	1	(electron with beam with lithography with tool) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:53

S7	3	(electron with beam with lithography with tool) and (equivalent with width)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:08
S8	0	((electron with beam with lithography with tool) and (equivalent with width)) and elongat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:00
S9	0	(electron with beam with lithography with tool) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:08
S10	10	(electron with beam with lithography) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:18
S11	4	((electron with beam with lithography) and (equivalent with width) and box and field) and pattern and cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:09
S12	67	(electron with beam with lithography) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:11
S13	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (elongat\$3 with space\$1) same (width with range))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12
S14	16	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12
S15	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:13
S16	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and (equivalent with width)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12

S17	5	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:26
S18	0	(pattern with test\$3 with cell) and (elongat\$3 with space\$1) and (width with range) and box and field and spot and border	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:28
S19	0	(pattern with test\$3 with cell) and (elongat\$3 with space\$1) and (width with range) and border	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29
S20	13	(pattern with test\$3 with cell) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29
S21	0	((pattern with test\$3 with cell) and (elongat\$3 with space\$1)) and (lithography with tool)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29
S22	23	electron with beam with lithography with tool with image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:39
S23	2	"6654703".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:33
S24	14	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:46
S25	4	((image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:27
S26	0	((image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)) and lithography and (test\$3 near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 21:02

S27	0	((image with quality with evaluat\$3) and (test\$3 near2 array) and (sub-field or subfield)) and lithography and (test\$3 near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:52
S28	0	((image with quality with evaluat\$3) and (test\$3 near2 array) and (sub-field or subfield)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 21:03
S29	0	(electron with beam with lithography) and (equivalent with width) and (test\$3 with pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:02
S30	1	(electron with beam with lithography) and (equivalent with width) and test\$3 and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:02
S31	0	(electron with beam with lithography) and (equivalent with width) and box and field and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:28
S32	0	(electron with beam with lithography) and (equivalent with width) and field and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:19
S33	0	(electron with beam with lithography) and (equivalent with width) and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:19
S34	5	(electron with beam with lithography) and (equivalent with width) and (length\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:21
S35	0	((electron with beam with lithography) and (equivalent with width) and (length\$3 with space)) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:21
S36	5	((electron with beam with lithography) and (equivalent with width) and (length\$3 with space)) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:22

S37	0	((electron with beam with lithography) and (evaluat\$3 with quality with image)) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:29
S38	2	((electron with beam with lithography) and (evaluat\$3 with quality with image)) and (array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:29
S39	6	(electron with beam with lithography) and (evaluat\$3 with quality with image)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:32
S40	3	lithography and (evaluat\$3 with quality with image) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 12:59
S41	2	lithography and (evaluat\$3 with quality with image) and polynomial	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:41
S42	5	lithography and (evaluat\$3 with quality with image) and (correct\$3 with field with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 13:09
S43	0	(lithography with tool) and (tool with correction with select\$3 with field with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:53
S44	0	(lithography with tool) and ((tool with correction) same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:07
S45	0	(lithography with tool) and (correction same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:54
S46	16	lithography and (correction same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55

S47	0	(lithography and (correction same (select\$3 with field with position))) and (record\$3 with test\$3 with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55
S48	0	(lithography and (correction same (select\$3 with field with position))) and (test\$3 with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55
S49	5	(lithography and (correction same (select\$3 with field with position))) and (image with quality)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:31
S50	22	"702"/\$.ccls. and (image with quality with evaluat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:34
S51	0	("702"/\$.ccls. and (image with quality with evaluat\$3)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:34
S52	1	("702"/\$.ccls. and (image with quality) and lithography) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:35
S53	22	"702"/\$.ccls. and (image with quality) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:36
S57	0	(test with pattern with cell) and shape-in-shape and box-in-box and (blank with pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:34
S58	26	(test with pattern with cell) and (blank with pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:43
S59	2	(test with pattern with cell) and (blank near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:50

S60	362	(test with pattern with cell) and (test near2 array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:01
S61	0	S60 and (sub-field or subfield) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:56
S62	1	S60 and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:52
S63	1	S60 and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:53
S64	6	S60 and (test with position) and substrate and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:58
S65	6	S60 and (test with position) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:58
S66	162	(test with pattern with cell) and (test near2 array) and (wafer or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:06
S67	22	S66 and (test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:02
S68	324	(test with pattern with cell) and (test near2 array) and (wafer or mask or semiconductor or chip)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:16
S69	0	S68 and (image with quality with evaluat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:08

S70	12	S68 and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:52
S71	0	(lithography with tool) and (range with elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:08
S72	0	(pattern adj cell) and (range with elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:09
S73	10	(pattern adj cell) and (elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:09
S74	2	(test with pattern with cell) and (test near2 array) and (wafer or mask or semiconductor or chip) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:17
S75	0	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:21
S76	60	(image with quality with evaluat\$3) and (test\$3 array) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:28
S77	0	(image with quality with evaluat\$3) and (test\$3 array) and (width with space\$1) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:08
S78	15	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:29
S79	0	(image with quality with evaluat\$3) and (test\$3 array) and ((sub-field or subfield) with test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:42

S80	3	(image with quality with evaluat\$3) and (test\$3 array) and ((sub-field or subfield) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:32
S81	0	(image with quality with evaluat\$3) and (test\$3 array) and (pattern near2 cell) and ((sub-field or subfield) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:32
S82	1	(image with quality with evaluat\$3) and (test\$3 array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:35
S83	0	(image with quality with evaluat\$3) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:36
S84	1	(image with quality) and (test\$3 array) and ((sub-field or subfield) with test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:42
S85	0	(image with quality) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:43
S86	0	(image with evaluat\$3) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:43
S87	2	(test\$3 with array) and (lithography with test\$3) and image and (test with position) and (test with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:39
S88	4	(test\$3 with array) and lithography and (test\$3 with correct\$3) and image and (test with position) and (test with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:44
S89	2	(test\$3 with array) and lithography and (test\$3 with correct\$3) and image and (test with position) and (test with cell) and (image with quality)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:48

S90	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and (test\$3 with correct\$3) and (test with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:50
S91	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:51
S92	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:51
S93	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:52
S94	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and lithography and correct\$3 and (test\$3 with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:07
S95	0	(evaluat\$3 near2 image near2 quality) and (test\$3 with array) and lithography and correct\$3 and (test\$3 with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:52
S96	1	(evaluat\$3 near2 image) and (test\$3 with array) and lithography and correct\$3 and (test\$3 with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:55
S97	0	((evaluat\$3 near2 image) same (field with position)) and (test\$3 with array) and lithography and substrate and correct\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:57
S98	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography and substrate and correct\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:58
S99	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:59

S10 0	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 19:00
S10 1	11	(evaluat\$3 with image) and (field with position) and (test\$3 with array) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 19:00
S10 2	0	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield) and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:47
S10 3	0	(image with quality with evaluat\$3) and array and (sub-field or subfield) and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:48
S10 4	0	(image with quality with evaluat\$3) and array and field and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:48
S10 5	6	(image with quality with evaluat\$3) and field and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S10 6	3	("5409538" "5790254" "5968691"). PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/19 21:50
S10 7	0	S106 and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S10 8	0	S106 and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S10 9	0	S106 and (high\$3 with quality) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:53

S11 0	0	S106 and (high\$3 with image) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:53
S11 1	0	S106 and (accuracy with quality) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:54
S11 2	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and (astigmatism with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:07
S11 3	14	(image with quality with evaluat\$3) and (test\$3 array) and (astigmatism with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 12:01
S11 4	9	(image with quality with evaluat\$3) and (test\$3 array) and (astigmatism with correction) and (focus with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 12:02
S11 5	6	(lithography with tool) and (elongat\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:44
S11 6	51	(lithography with tool) and box-in-box	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:10
S11 7	20	S116 and (box-in-box near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:11
S11 8	4	S117 and elongat\$3 and space	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:13